

Effect of temperature on thickness and Resistivity of II-VI solid solution of CdSe_{0.75}Te_{0.25} thin films by spray pyrolysis

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ABSTRACT

CdSe_{0.75}Te_{0.25} thin films deposited by spray pyrolysis using aqueous solution of cadmium chloride, selenium dioxide and Tellurium tetrachloride of 0.02 M of each at different substrate temperature. From the resistivity against inverse temperature activation energy calculated. It was observed that activation energy decreases as temperature increases. But thickness of the films increases, if the temperature of the films increases upto the optimum temperature. It indicates the increases of grain size of the thin films and grain boundary width decreases. This may be due to the oxygen acceptor level are very shallow from the conduction band.

Keywords :- CdSe_{0.75}Te_{0.25}, Thin films, resistivity.

1. INTRODUCTION

Transport phenomenon in II-VI compound and their solid solutions are as important as their optical properties and they provide valuable information about the nature of carriers and scattering mechanisms. These films of CdSe_xTe_{1-x} are used in the fabrication of transistors, solar cells, and photoconductors. There are other applications are variable gap structures and photodetectors. The very few workers work on CdSe_xTe_{1-x} thin films deposited on glass substrate. The Hall mobilities of charge carriers in the binary compounds are known to be limited by Piezoelectric/optical mode/ impurity scattering in different degree at low temperature (1). Belyaev et al have studied Hall mobility and resistivity by the heat screen method. They have taken the measurement in the 100 K-300 K. Uthanna & Reddy (2) have reported the dependence of electrical resistivity and Hall mobility on the percentage of selenium present in the compounds. They state that resistivity decreases exponentially with x and Hall mobility increases with x.

There are several methods to prepare thin films, such as chemical vapour deposition, flash evaporation, vacuum evaporation, r.f. sputtering. We have chosen the spray pyrolysis method due to its simplicity, inexpensiveness, and ease of handling to prepare thin films of CdSe_xTe_{1-x} and study the effect of temperature on resistivity and thickness of the films.

The aim of the work is to prepare the CdSe_{0.75}Te_{0.25} thin films at different temperatures. The temperature response on resistivity measurements were carried out in the temperature range 300 K to 473 K in an atmosphere environment and also seen the effect on thickness of the films.

2. PREPARATION OF THE SAMPLE

Thin films of CdSe_{0.75}Te_{0.25} were prepared by using an aqueous solution of cadmium chloride, selenium dioxide and Tellurium tetrachloride each of 0.02 M at 350°C on the pre-heated glass substrate. Chemicals were used as AR-Grade. These three solutions are mixed and inserted into the sprayer. Now the sprayer sprays the mixed solution on the pre-heated glass substrate. The sprayer is moved to and fro to avoid the formation of droplets on the substrate and to ensure instant evaporation. The solution was taken in the ratio 1:2.2 by volume to obtain the desired CdSe_{0.75}Te_{0.25} thin films. The films show selenium or Tellurium deficiency (2-4) if the ratio of the solutions was taken in the ratio 1:1. The spray rate was maintained at 3.5 ml/min and pressure also kept constant at 12 kg/cm². The temperature of the substrate was calculated by a pre-calibrated copper-constantan thermocouple. Thicknesses of the films were calculated by Michelson interferometers. Electrical resistivity was measured by the Four-Probe method (5). The temperature of the substrate varied from 300°C to 375°C in the interval of 25°C.

3. MEASUREMENT OF THICKNESS

The thickness of the CdSe_{0.75}Te_{0.25} thin films was determined by a Michelson interferometer. Table 1 shows the variation of thickness with substrate temperature. It was observed that if the temperature of the substrate increases from 300°C to 350°C, the thickness of the films also increases but if further increases of temperature say 375°C, the thickness of the films decreases. This is due to higher evaporation of the initial ingredient (6-7).

4.ELECTRICAL PROPERTIES

The type of conductivity of all films tested by hot-Probe method was of n-type semiconductor. The resistivity was calculated of all the films for the temperature range 300 K to 375⁰ K using the relation,

$$\rho = 2\pi s V/I /G_7 (t/s) \quad (1)$$

$$\text{and } G_7(t/s) = 2s/t \ln (2)$$

Where s-the distance between the probes, t-the thickness of the films. I-the current generated from constant current source between the inner probes from the constant current source ,v-the voltage developed between the outer probes.

Fig.2 shows the electrical resistivity verses inverse temperature of CdSe_{0.75}Te_{0.25} thin films of different temperature of as deposited.

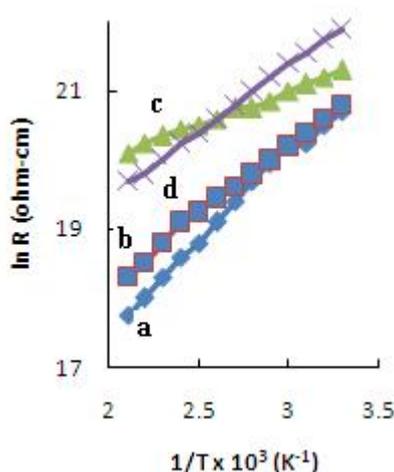


Fig. 1. Shows the resistivity verses inverse temperature of as deposited CdSe_{0.75}Te_{0.25} thin films at different temperature a) 300 °C, b) 325 °C, c) 350 °C and d) 375 °C

It was observed that resistivity increases as if the temperature is lowered. The resistivity also increases if the deposition temperature increases. This is due to the capturing of the free electrons from the conduction band will reduce the number of free electrons available for the electrical conduction (8). Hence resistance of the films increases. From the graph of figure 2, activation energy also calculated .It was observed that the preparation temperature increases the activation energy also decreases. Table.1 shows the variation of activation energy, thickness with different deposition temperature.

Table .1.

Temperature °C	Thickness t(μm)	Activation energy E _a (eV)
300	0.2018	283
325	0.2215	290
350	0.2530	305
375	0.2330	325

The increase of temperature, the activation energy decreases. This is due to very shallow from the conduction band. Kalinkin etal have reported the films heated in vacuum at temperature above 280 K the process of conduction in CdSe_xTe_{1-x} solid solution films is due to the activation energy of charge carriers from deep levels to the conduction band. When the thickness of the films increases, the grain size of the films increases and grain boundary width decreases. Hence also the impurity levels becomes less deep. The indicates the decrease in activation energy with an increase in the films thickness, the energy needed for the activation of charge carriers to the conduction band is reduced.

5.CONCLUSION

CdSe_{0.75}Te_{0.25} thin films prepared by spray pyrolysis method. It was observed the thickness of the films increases if the temperature increases upto optimised temperature 350⁰C. After this increase of temperature the thickness decreases. On the other hand activation energy continuously decreases if increase of temperature. This is due to increase of grain size of the films, which reduces grain boundary width.

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